# Status of GEM production in KOREA



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# Introduction to GEM production team & Facility



#### Introduction



#### • KOREA GEM production team

University of Seoul : 1 Prof , 1 post-doc , 1 engineer ,1 Ph.D student



Mecharo : 2 Manager , 1 engineer , 1 technician

#### • Production site

- R&D and Production Facility
- Clean room :  $1300 \text{ m}^2$





#### Facility



#### • Production room A for small-size GEM foils(<45x45cm)

A-room is for the R&D & small quantity order.





- Production room B for large-size GEM foils(<150x100cm)
  - B-room is for mass-production
    - & large size-order.
  - Also B-room has the machines for Q/C.
  - (Optical inspection, Current measure)







### A brief history of GEM production in KOREA

#### History



- A first version of GEM was produced in Nov.2012.
  - We developed by own production method double side litho + Cu etching + PI etching
- KOREA team and CERN signed the MOU for the GEM tech in July 2013.
  - We started producing HD GEM since then.
  - Uniformity is σ<2μm.</li>
    - Presented in MPGD2013
- We made a first version of Large GEM in Dec.2013.
- 10 x 10 Gain calibration at CERN in Feb.2014.



• Ongoing work :: 30x30 Gain calibration at CERN ,comic muon detector build at UOS





## **GEM production by Double mask method**



#### **Double Mask Process**







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1<sup>st</sup> test sample(July.2014) :: first try to make a large GEM foil with the double-side method. N ot successful due to bad mask attachment.

2<sup>nd</sup> test sample(Aug.2014) :: successful UV exposure was achieved. Problems with hole shape s on some areas

3<sup>rd</sup> test sample(Sep.2014) :: perfect UV exposure, perfect hole shape, precision hole-to-hole al ignment achieved

- conclusion: we can do it! (if we can use this large lithography machine for production)





## GEM production by Single mask method



#### Single Mask Method





- 1. Raw material
- 2. Top Cu Hole Etching
- 3. PI Etching
- 4. Bottom-Cu Laminating for Protection
- 5. Bottom-Cu Electro Etching
- 6. Remove Laminating Film
- 7. Second PI Etching







#### Summary



- We successfully developed a large size GEM foil production method using double-side etching technology
- Need to buy a \$1M machine for large size UV lithography machine. we are studying to production by single mask method.
- For Mass production, We have to reduce human's operation on stream.
  - » Electro-Cu etching step need to manpower in single mask process.
- We are producing 150 GEM foils(10x10) & 50 cathode in KOREA. It's check point for rate of production.





- We'll finalise the single mask production study shortly. By the end of this year, we'll have both methods (double-side and single-side) in hands!
- Future plan for productions: 100 10x10 small GEM foils (mid 2015), ship 50 foils to Rui
  10 GE11 GEM foil test production and QC (late 2015)
  20 or more GE11 GEM foil production (early 2016) for YETS 2016-2017.





# Thank you





## **Back Up**

























#### CERN-GEM vs KCMS-GEM



#### • 10x10 Gain Calibration from CERN (2014/02/17)

